Special Issue

Advancements in Low-Dimensional Materials: Focus on Detailed Methodologies

Message from the Guest Editors

Low-dimensional materials exhibit a wide range of new properties that can be employed to fabricate improved and novel devices. The ongoing research on these materials is advancing electronics, materials science, and related fields. We would like you to consider submitting a manuscript in this field that provides detailed and rigorous methodologies or processes, as these are crucial for advancing the field and ensuring replicability and robustness in research findings.

Guest Editors

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Deadline for manuscript submissions

25 September 2025

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Editor-in-Chief

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